

Evaluation of suprathermal ions in a laser-produced plasma beyond-EUV source

Takeru Niinuma,¹ Tsukasa Sugiura,¹ Masaki Kume,¹ Yuto Nakayama,¹ Hiroki Morita,¹

Atsushi Sunahara,² Shinichi Namba,³ and Takeshi Higashiguchi¹

¹Utsunomiya University, 7-1-2, Yoto, Utsunomiya, Tochigi 321-8585, Japan ²Center for Materials Under Extreme Environment, Purdue University, West Lafayette, Indiana 47907, USA ³Hiroshima University, 1-4-1 Kagamiyama, Higashihiroshima, Hiroshima 739-8527, Japan

Abstract

According to the latest international semiconductor roadmap, Gd plasma has been proposed for the next-generation [beyond-EUV (B-EUV)] light source at a wavelength of 6.x nm. This study is very important for debris mitigation to extend the life of C_1 mirror toward B-EUV lithography.

Objective

We evaluate the charge-separated energy spectra of suprathermal ions emitted from laser-produced Gd plasma for debris mitigation.

- We observe the maximum kinetic energy of fast Gd ions.
- We compare the effect of laser pulse duration on the kinetic energy of Gd ions.

Background







Previous study

- Wavelength from Gd plasma:
 6.x nm (Fig. 1).
- Highly reflective collecting mirror for 6.x nm (La/B₄C).

The characteristics of EUV emission from a Gd plasma are clear.



Sprathermal ion debris emitted from plasma is unclear (Fig. 2).

Issues

(a) Ion debris damage the C₁ mirror.(b) How high energy ions are there?



We focus on suprathermal ions from B-EUV source.





Conclusion & highlight





Experimental detail & discussion

Experimental detail



Discussion





Fig. 6. Laser intensity dependences of electron temperature at the laser wavelength of 1064nm.

Fig. 7. Laser pulse duration and laser intensity dependences of energy flow losses at the laser wavelength of 1064nm. Ref. H. Kawasaki et al., AIP Advances 10, 065306 (2020).



